



IN THE

UNITED STATES PATENT AND TRADEMARK OFFICE

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I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on the date shown below:

Dated: March 22, 2002

By:

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COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

AMENDMENT A

Dear Sir:

This amendment is in response to the Office Action mailed October 22, 2001, which established a shortened statutory period for response that expired on January 22, 2002. A two-month extension of time is included herewith.

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